



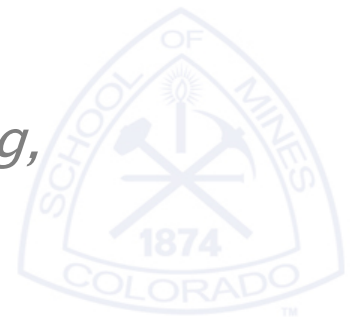
COLORADOSCHOOL OF **MINES**



ATOM PROBE AND (S)TEM ANALYSIS OF SEMICONDUCTOR AND OXIDE NANOSTRUCTURES

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Combined TEM and Atom Probe Tomography

▶ Advantages of TEM prior to atom probe analysis

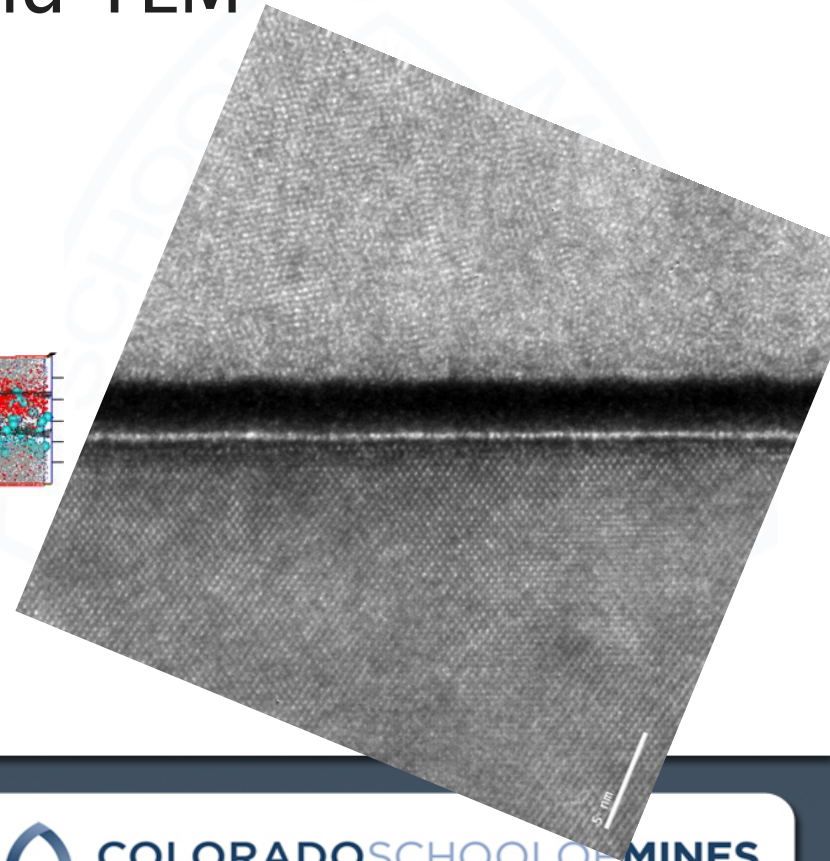
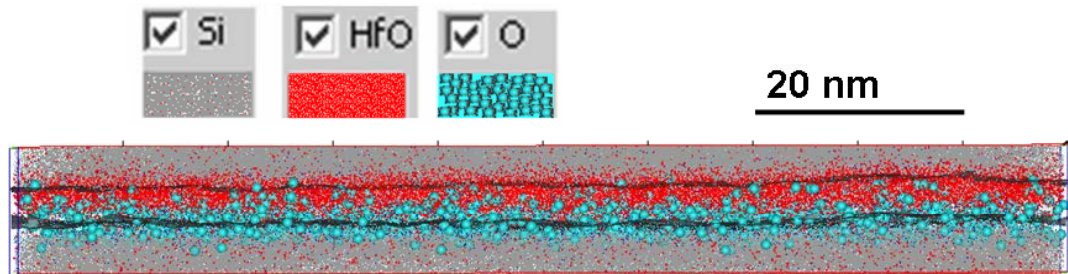
- Can verify feature of interest is contained in sample tip
- Direct measurement of shank angle, volume, layer spacing, etc. – assists in generating accurate reconstructions
- Direct determination of d-spacing, crystal structure, crystallographic orientation(s), and crystal defects

▶ Advantages of TEM after atom probe analysis

- Can determine tip shape resulting from analysis – assists in determining local field
- Can determine volume analyzed
- Assess analysis parameters

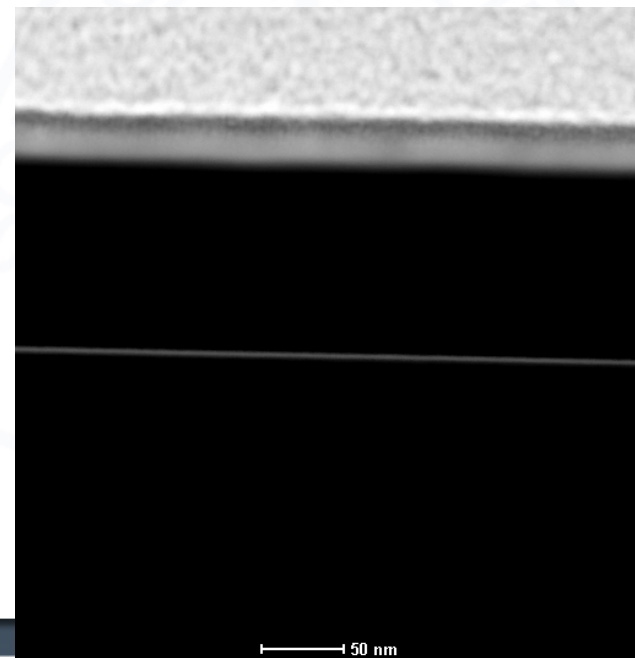
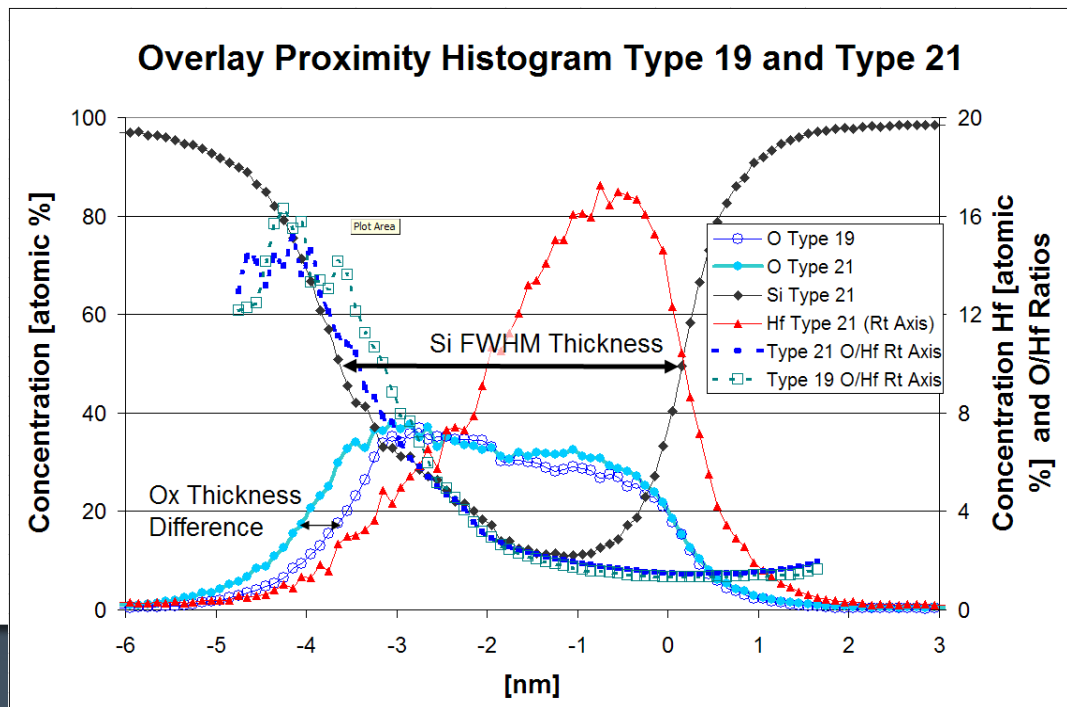
Co-examination of High-k stacks with APT and TEM

- ▶ Si / HfO₂ / poly Si stack
- ▶ Ex-situ (separate APT and TEM specimens)

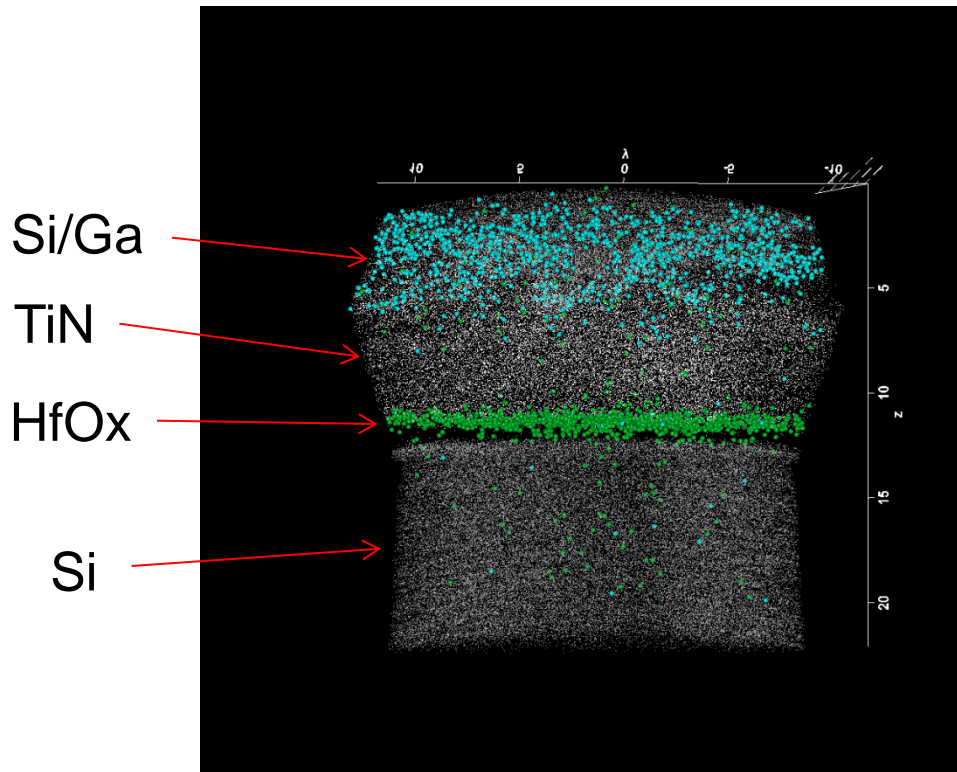


Co-examination of High-k stacks with APT and TEM

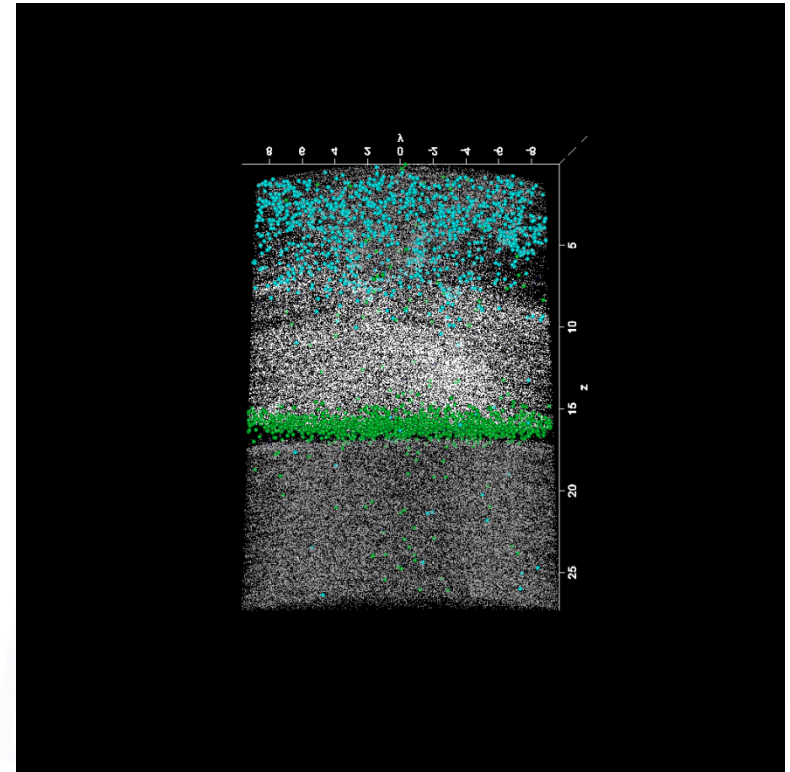
- ▶ Compared with HRTEM and STEM-HAADF, APT results in 25% thicker films
 - Reconstruction or Calibration issue?
 - Method of determination?
 - Sample variability?



High-k Stack Reconstruction Comparison

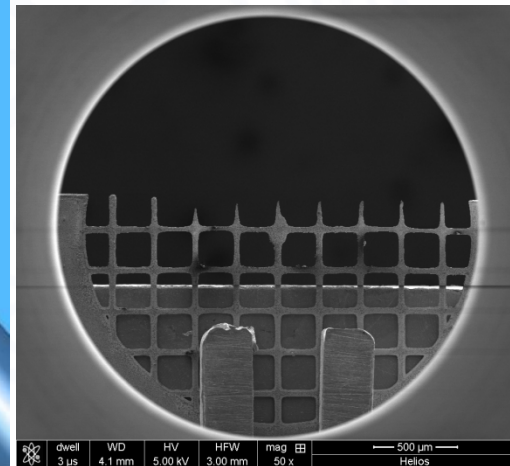
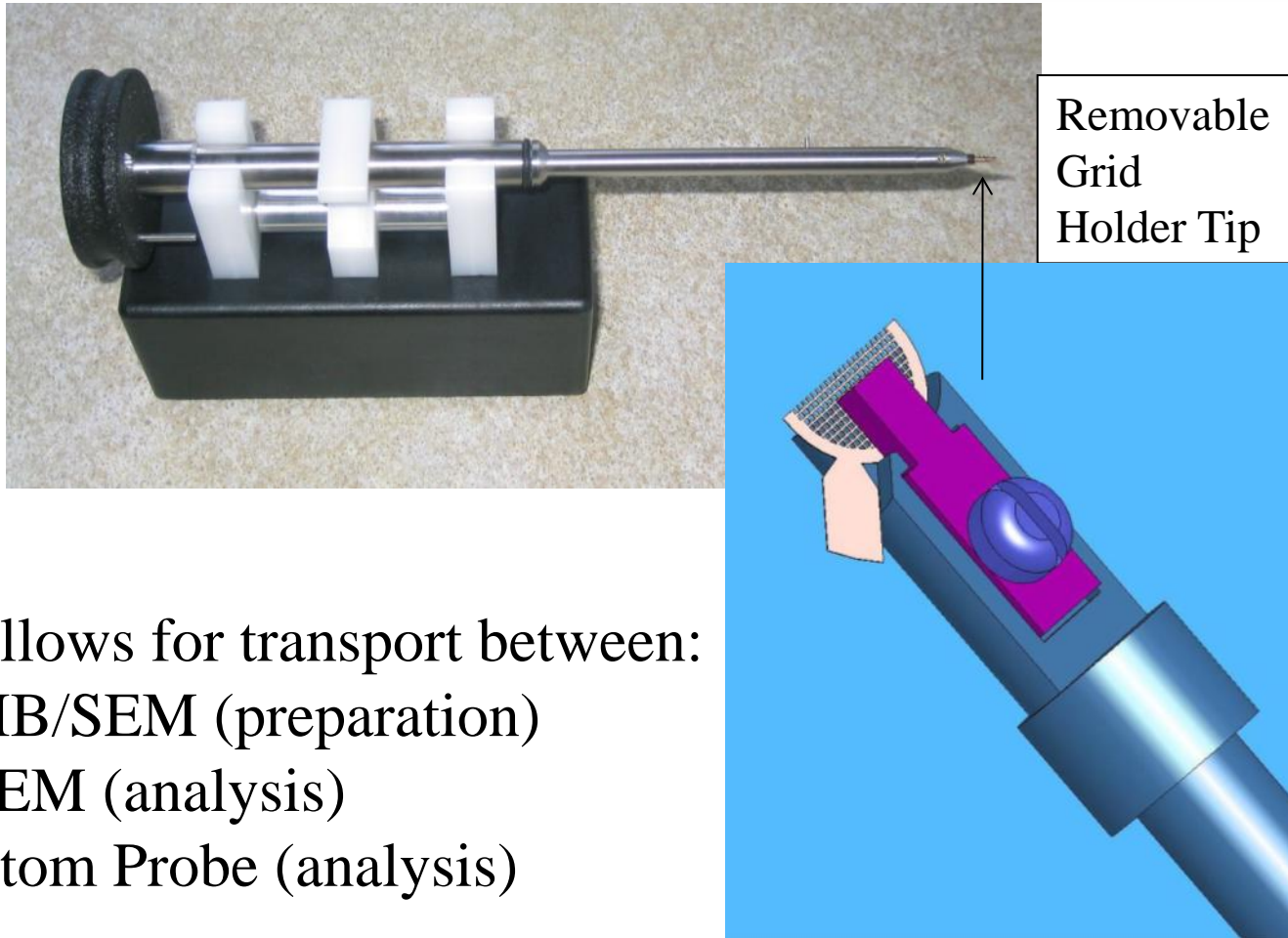


V/kr volume



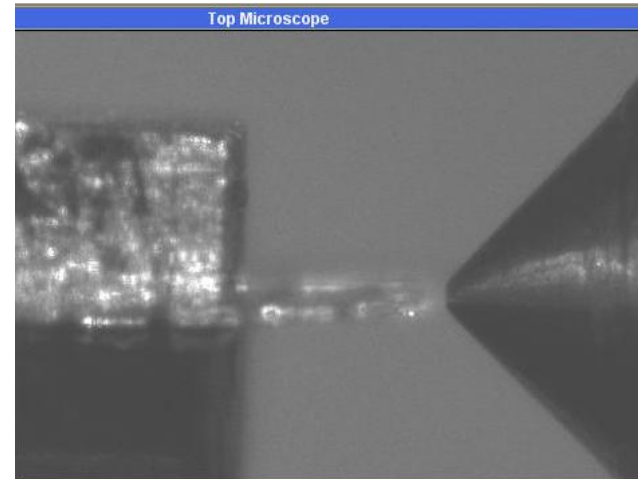
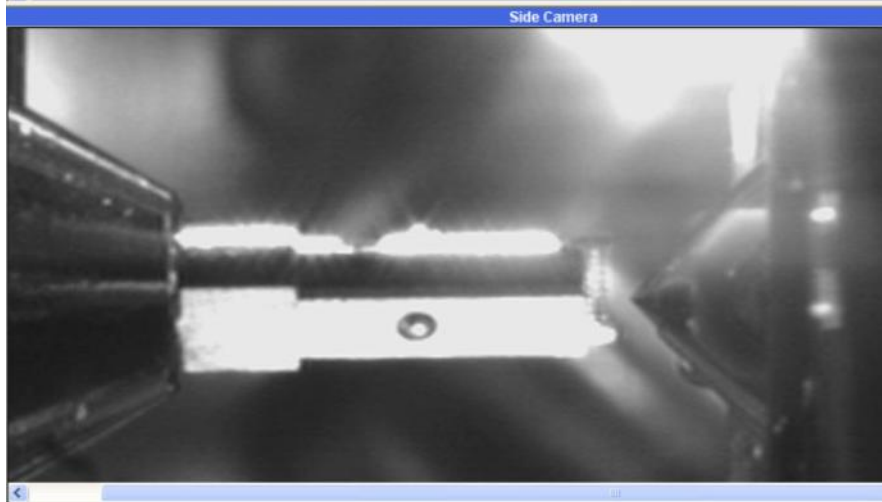
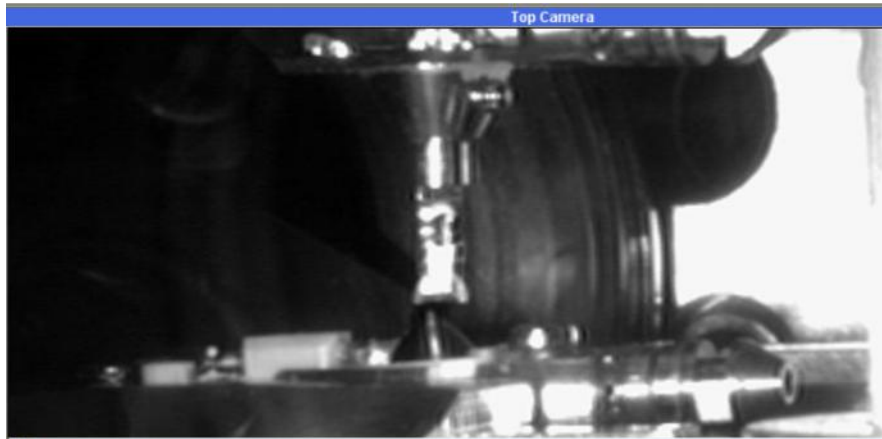
Volume from diameter,
constant shank angle

TEM and APT hardware



Allows for transport between:
FIB/SEM (preparation)
TEM (analysis)
Atom Probe (analysis)

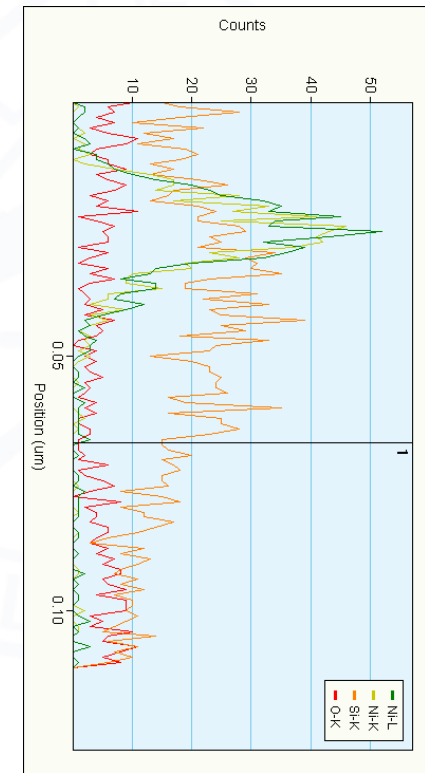
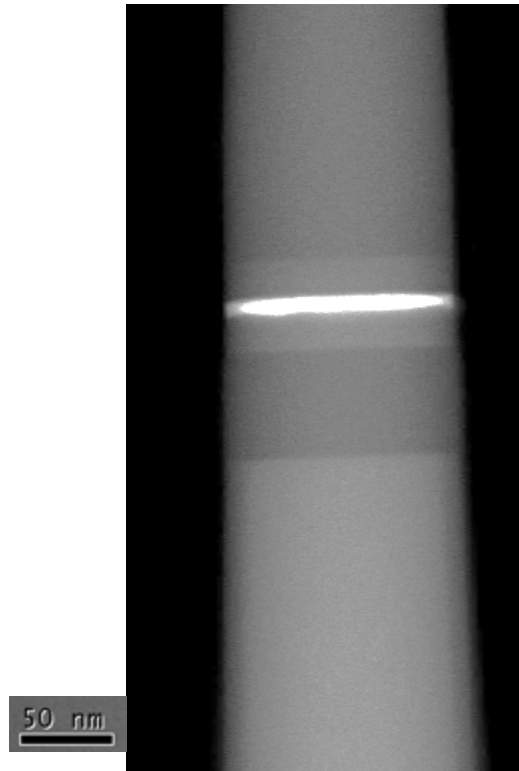
TEM and APT Hardware



Microelectronic stack

- ▶ Poly Si / NiSi / Si / SiO_x / Si stack

As-produced
APT specimen
(STEM-HAADF
and EDS)

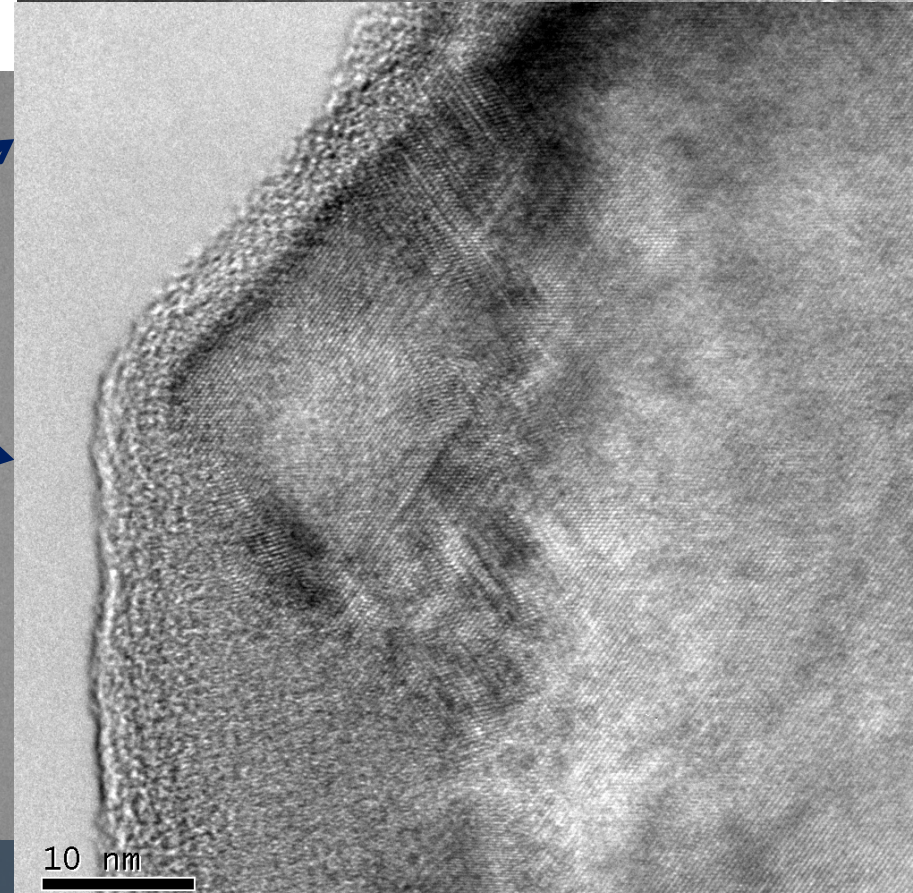
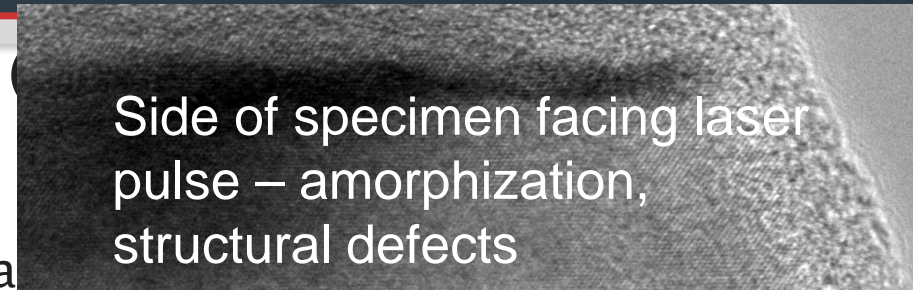
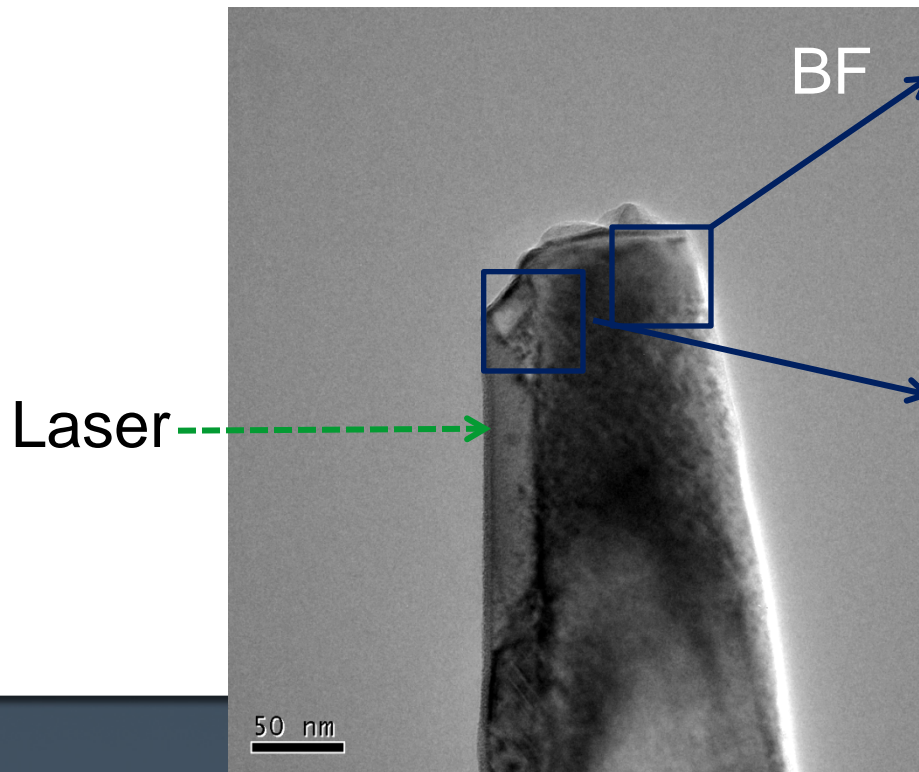


Post APT Analysis

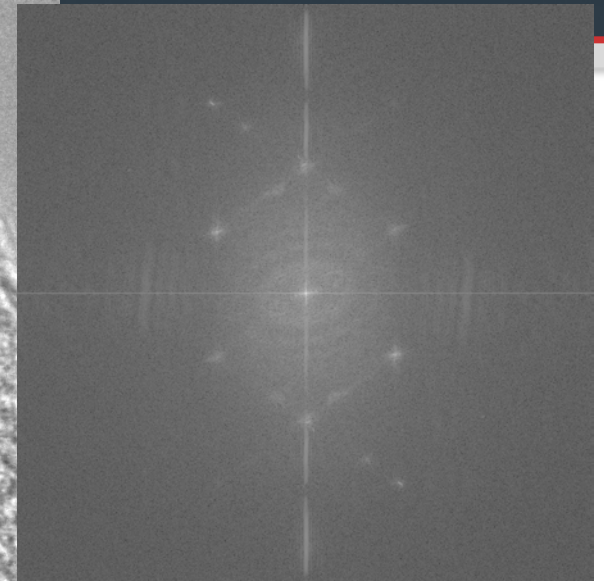
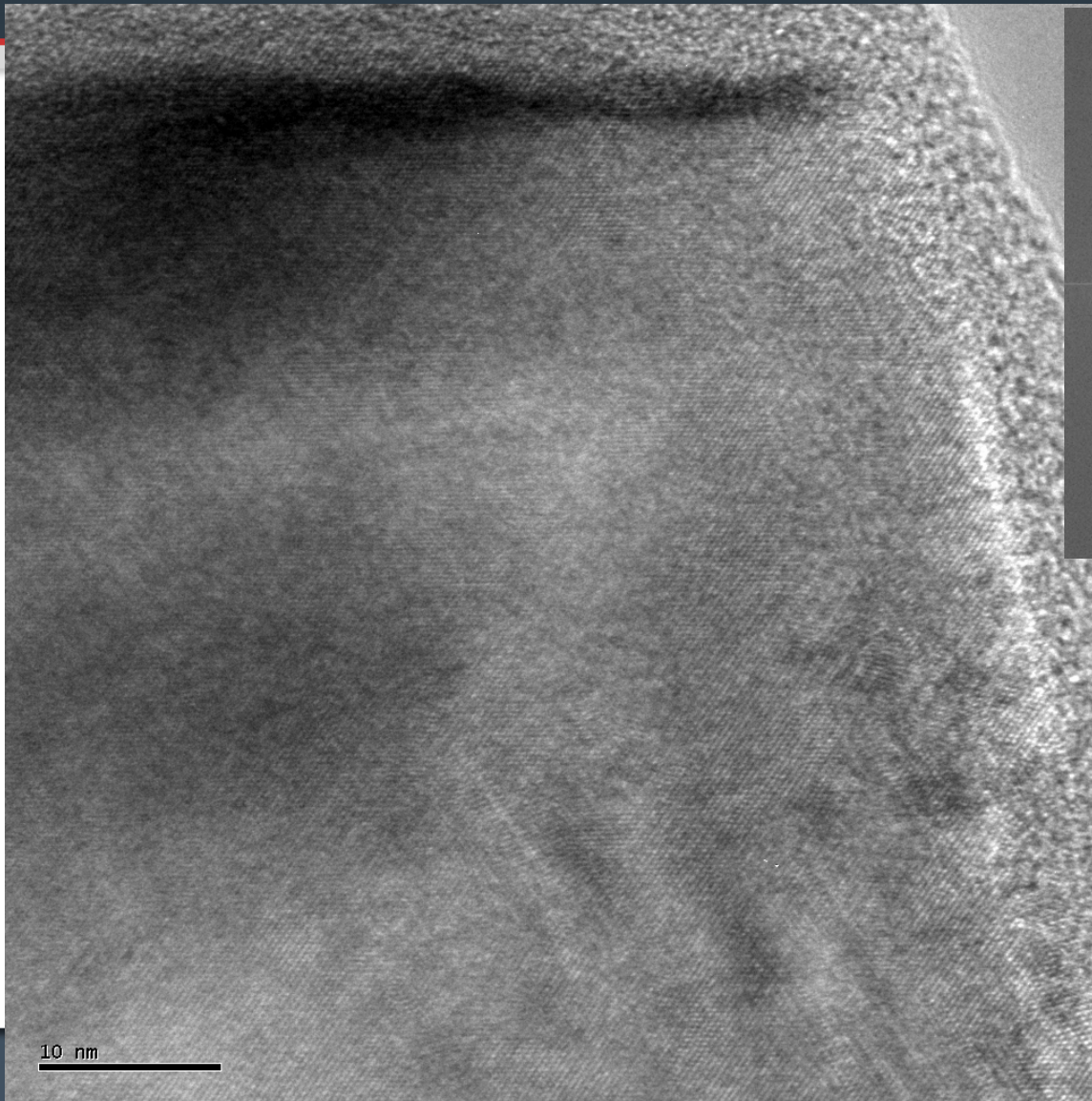
- ▶ After Laser Pulsed APT
 - Failure at Si / SiO_x interface
 - Significant morphological change

Side of specimen away from laser pulse – no damage

Side of specimen facing laser pulse – amorphization, structural defects

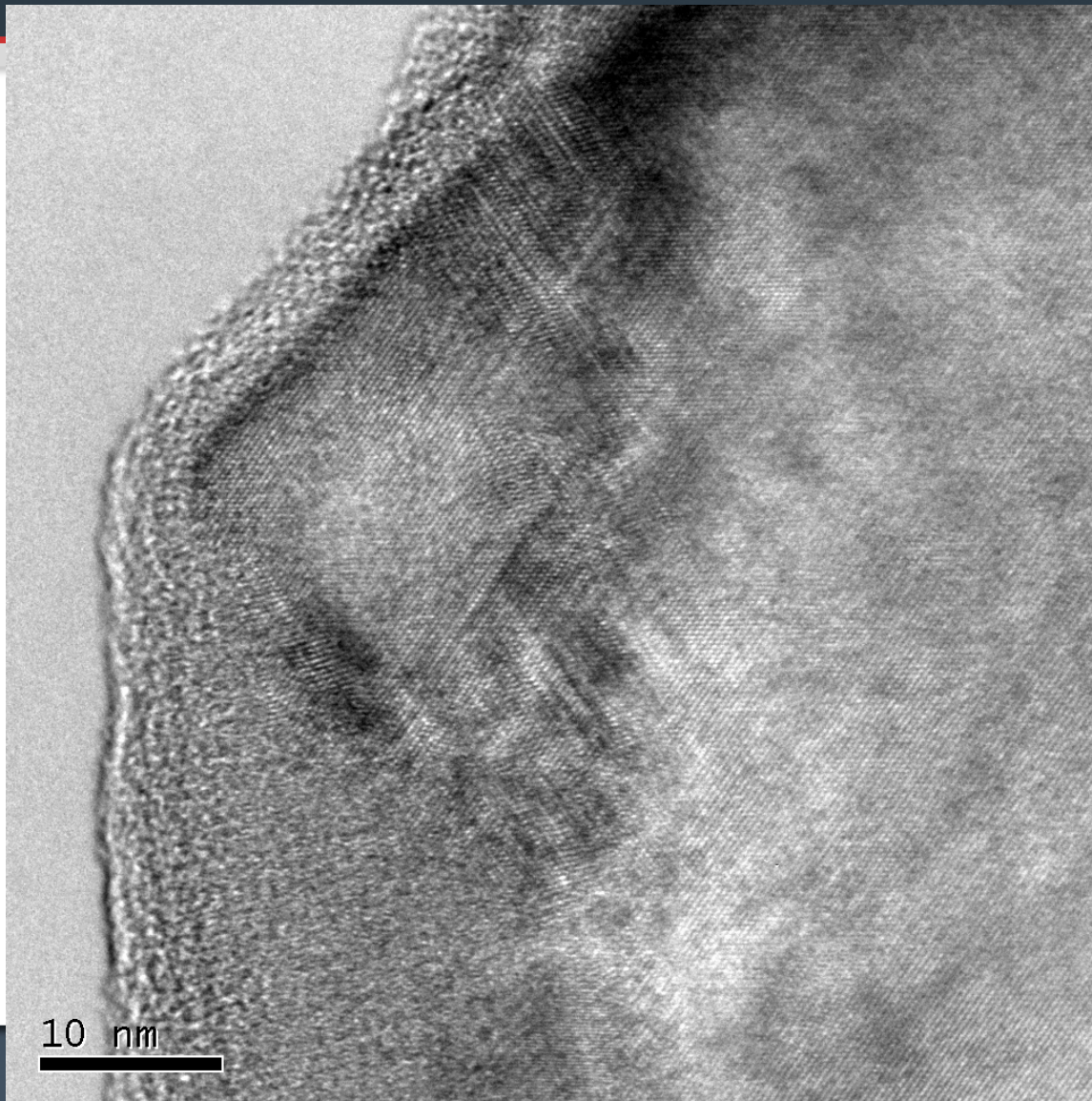


Post APT Analysis



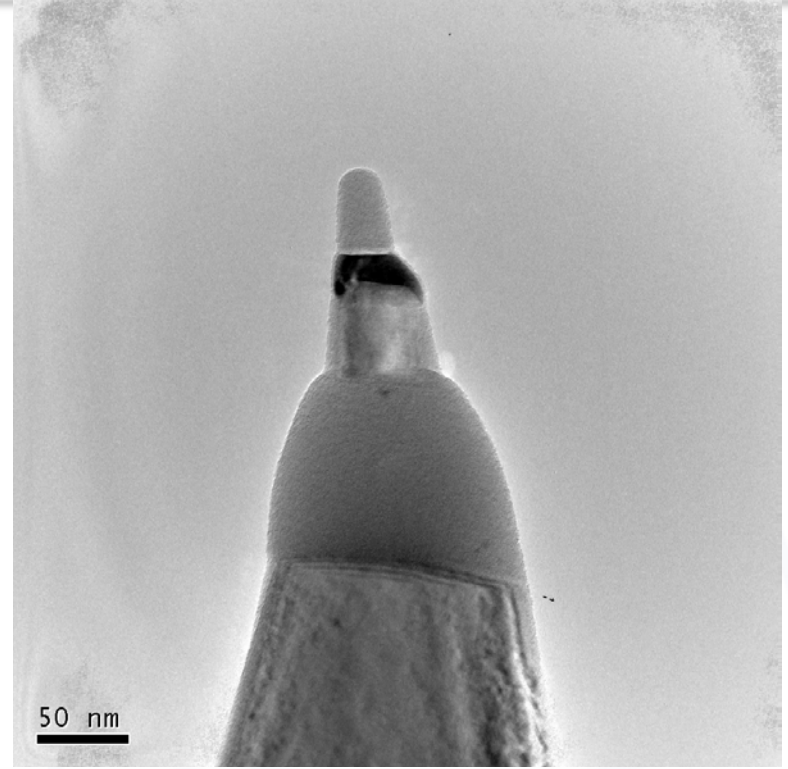
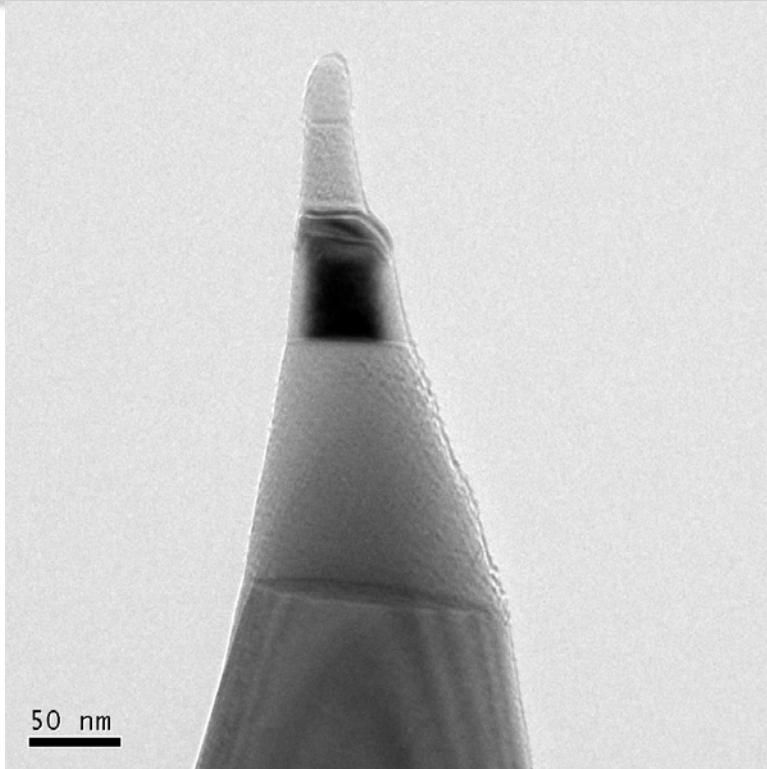
Top and Side of specimen away from laser pulse – no damage

Post APT Analysis



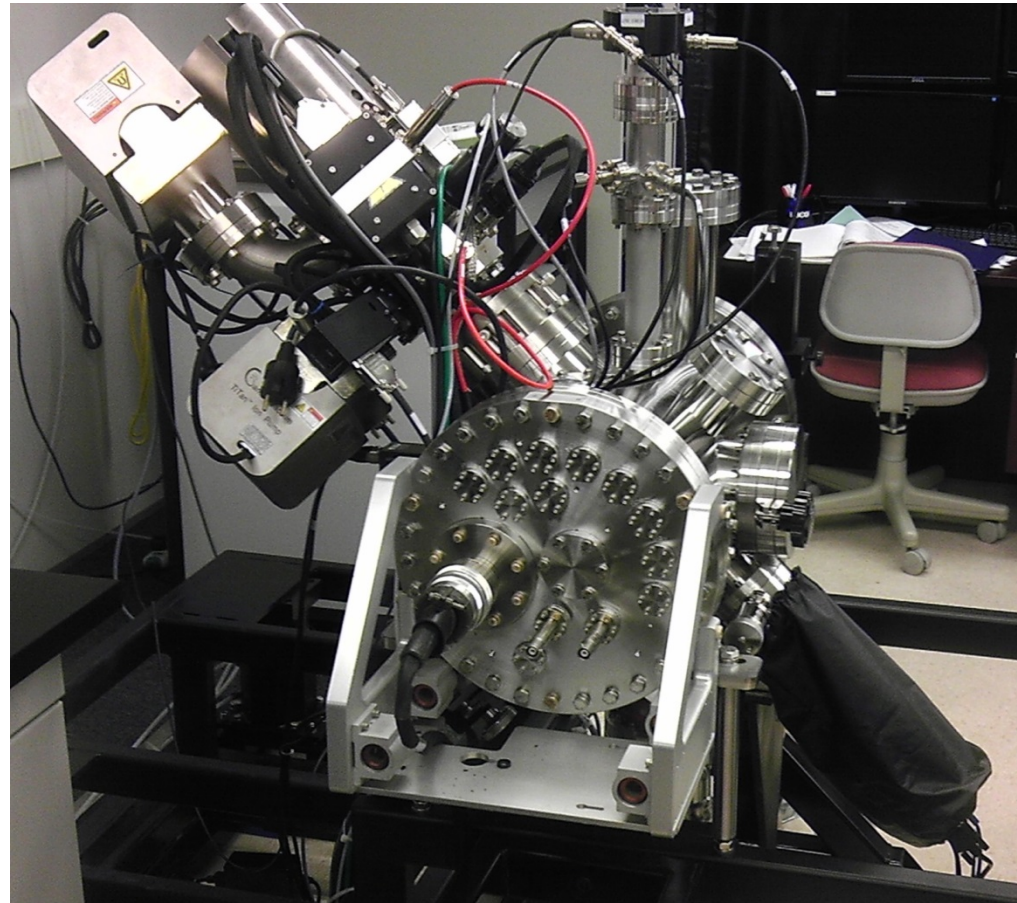
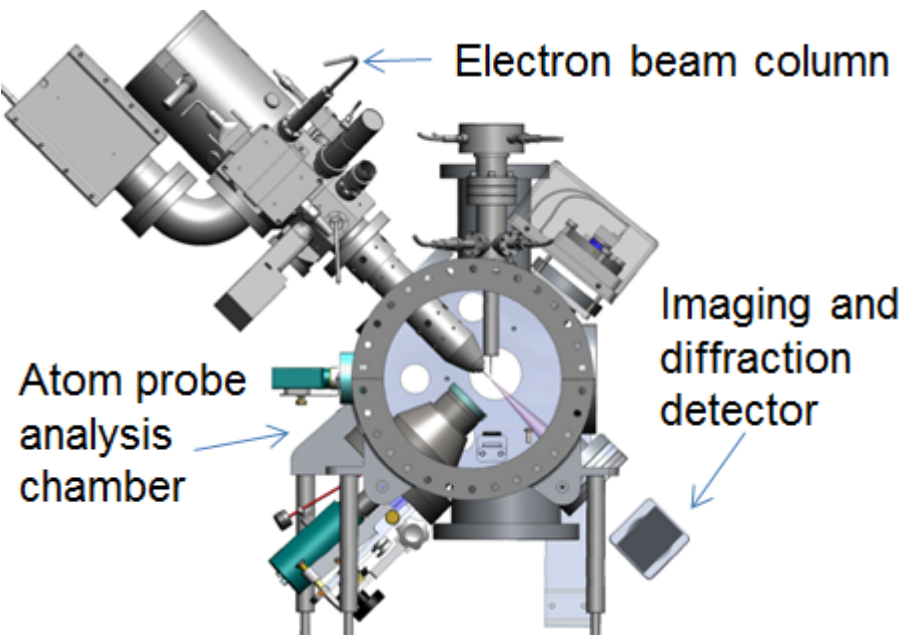
Top and Side of specimen facing laser pulse – amorphization, structural defects

Post APT Analysis – SOI



- ▶ Measurable evaporated material and uniform tip shape
- ▶ Significant changes in insulator layer

Dynamic Atom Probe – combined EM and APT in one instrument



This atom probe instrument is supported under NSF Award Number 1040456.

Correlative TEM and APT summary

- ▶ Can provide complementary information
- ▶ Can be used to assist in generating accurate reconstructions
- ▶ Can provide feedback on APT analysis conditions
- ▶ In-situ rapid thermal quenching and analysis.

Going forward

- ▶ How to best incorporate into atom probe data?
 - Provide dynamic feedback during analysis?
 - Adjust reconstruction after the analysis?
- ▶ Other methods of feedback / detection
 - Tip shape from laser scan
 - Species being detected
 - Uniformity of evaporation
 - Additional detectors / attachments